

Application No. 10/810,385 Inventor: Ming Lu et al. "Repair of Photolithography Mask By Sub-Wavelength..." Replacement Sheet 1 of 3

N1085-00222

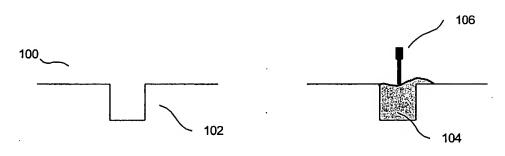


FIG. 1 (PRIOR ART)

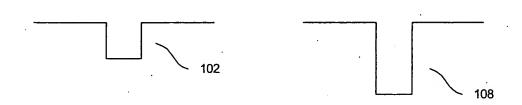


FIG. 2 (PRIOR ART)

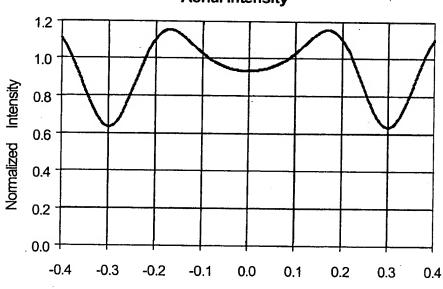


FIG. 3 (PRIOR ART)

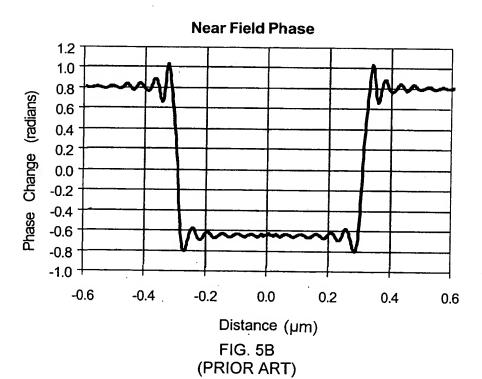
Application No. 10/810,385 Inventor: Ming Lu et al. "Repair of Photolithography Mask By Sub-Wavelength..." Replacement Sheet 2 of 3

N1085-00222

Aerial Intensity



Distance (µm) FIG. 5A (PRIOR ART)



N1085-00222

